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Development of MicroMEGAS using sputtered resistive electrodes for ATLAS upgrade

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New MPGD production method, forming resistive electrodes by metal/carbon sputtering, has been developed. Both fine electrodes structure (<50 micron) forming and large area production (>1mˆ2) are available using this method. The surface resistivity is controlled within a few tens percent of uniformity in the range of 100kΩ/sq. −10MΩ/sq. Those properties are very useful for ATLAS MicroMEGAS production. We will report the development status and test results of prototype MicroMEGAS using sputtered resistive anodes for ATLAS muon upgrade.

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